



Titanium Oxide Thin Films Using Plasma

This article shows a deposition method for thin films of titanium oxide that uses a plasma created in close proximity of the coating substrate. The quality of the plasma can be characterized by monitoring the optical emission using a high-resolution spectrograph.

Featured Paper/ Publication: [Fast formation of amorphous titanium dioxide thin films using a liquid-assisted plasma-enhanced deposition process in open air](#), Surface and Coatings Technology, 2018

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Products used: [Isoplane](#), [PIXIS](#)

